- 44. A laser irradiation apparatus of claim 42, wherein said laser oscillator is a member selected from the group consisting of an excimer laser, a YAG laser and a glass laser.
- 45. A laser irradiation apparatus of claim 42, wherein said laser oscillator is a member selected from the group consisting of a YVO₄ laser, a YLF laser and an Ar laser.
- 46. A laser irradiation apparatus for forming a laser beam elongated in one direction on an irradiated surface, comprising:

a laser oscillator; and

two reflectors for splitting said laser beam, each including a plurality of reflective surfaces.

- 47. A laser irradiation apparatus of claim 46, wherein said laser beam has a length of 600 mm or more along said one direction on said irradiated surface.
- 48. A laser irradiation apparatus of claim 46, wherein said laser oscillator is a member selected from the group consisting of an excimer laser, a YAG laser and a glass laser.
- 49. A laser irradiation apparatus of claim 46, wherein said laser oscillator is a member selected from the group consisting of a YVO₄ laser, a YLF laser and an Ar laser.
- 50. A laser irradiation apparatus for forming a laser beam elongated in one direction on an irradiated surface, comprising:

a laser oscillator;

a first reflector for splitting said laser beam, said first reflector including a plurality of reflective surfaces; and

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a second reflector for splitting said laser beam, said second reflector including a plurality of plane mirrors.

- 51. A laser irradiation apparatus of claim 50, wherein said laser beam has a length of 600 mm/or more along said one direction on said irradiated surface.
- 52. A laser irradiation apparatus of claim 50, wherein said laser oscillator is a member selected from the group consisting of an excimer laser, a YAG laser and a glass laser.
- 53. A laser irradiation apparatus of claim 50, wherein said laser oscillator is a member selected from the group consisting of a YVO₄ laser, a YLF laser and an Ar laser.--

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